~~Amendment under Article 34,~~CLAIMS

1. A chemical mechanical slurry composition comprising: abrasive particles, water, azole compounds and piperazine, and further comprising tetramethylammonium hydroxide.
2. The slurry composition according to claim 1, wherein the abrasive particle is one or more selected from SiO_2, Al_2O_3, CeO_2, SiC and Si_3N_4.
3. The slurry composition according to claim 1 or 2, wherein the abrasive particle is present in an amount ranging from 1-20 weight percent.
4. The slurry composition according to claim 1, wherein the azole compound is one or more selected from triazole, tetrazole and derivatives thereof.
5. The slurry composition according to claim 4, wherein the azole compound is one or more selected from 1,2,4-triazole, 3-amino-1,2,4-triazole, 5-amino-1,2,4-triazole, 5-carboxy-3-amino-1,2,4-triazole and benzotriazole, 1-H-tetrazole, 5-aminotetrazole.
6. The slurry composition according to claim 1, wherein the azole compound is present in an amount ranging from 1-8 weight percent.
7. The slurry composition according to claim 1, wherein the piperazine is present in an amount ranging from 1-10 weight percent.
8. The slurry composition according to claim 1, wherein the tetramethylammonium hydroxide is present in an amount ranging from 1-10 weight percent.
9. The slurry composition according to claim 1, having a pH value equal to 9-12.
10. The slurry composition according to claim 1-9, providing slurry composition for polishing single-crystal or poly-crystal silicon.